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BY APPLICANT	EMENT	APPLICANT Todd et al.				
	SARY)	FILING DATE February 11, 2002	GROUP 1762			
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FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT	ATTY, DOCKET NO. ASMEX.281A	APPLICATION NO. 10/074,583
BY APPLICANT	APPLICANT Todd et al.	
(USE SEVERAL SHEETS IF NECESSARY)	FILING DATE February 11, 2002	GROUP 1762

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FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY, DOCKET NO. ASMEX.291A	APPLICATION NO. 10/074,563	
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SHEET 1 OF 1 U.S. DEPARTMENT OF COMMERCE ATTY, DOCKET NO. APPLICATION NO. **FORM PTO-1449** PATENT AND TRADEMARK OFFICE ASMEX.291A 10/074,563 INFORMATION DISCLOSURE STATEMENT BY APPLICANT OIPE APPLICANT Todd et al. SEVERAL SHEETS IF NECESSARY) FILING DATE **GROUP** February 11, 2002 PADEMARY **U.S. PATENT DOCUMENTS EXAMINER** DOCUMENT NUMBER DATE NAME CLASS SUBCLASS FILING DATE INITIAL (IF APPROPRIATE) 6,159,828 12/12/00 Ping et al. 438 486 THAM 6,171,662 B1 01/09/01 Nakao 427 595 THOM 6,197,669 B1 03/06/01 Twu et al. 438 585 **FOREIGN PATENT DOCUMENTS EXAMINER** DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS **TRANSLATION** INITIAL YES NO EXAMINER INITIAL OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.) S:\DOCS\JOM\JOM-4096.DOC:112102

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FORM PT<sub>2</sub>2-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE ATTY. DOCKET NO. ASMEX.291A

APPLICATION NO. 10/074,563

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

**APPLICANT** Todd et al.

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FILING DATE February 11, 2002

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SHEET 2 OF 2 ATTY, DOCKET NO. FORM PTQ-1449 U.S. DEPARTMENT OF COMMERCE APPLICATION NO. GROUP 202002

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